

Supporting Information

Confining the growth of mesoporous silica films into nanospaces: towards surface nanopatterning

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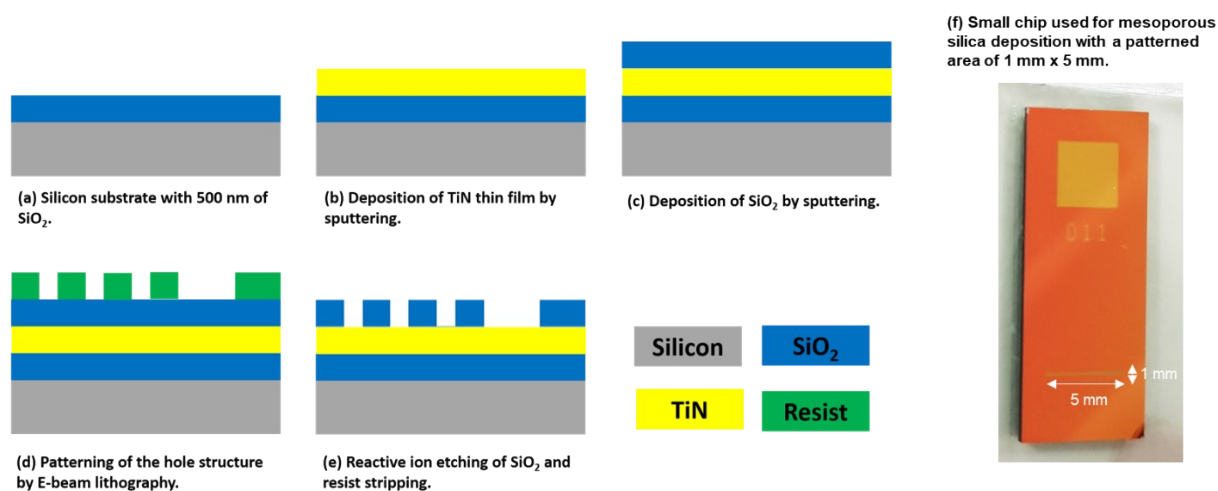


Figure S1- Fabrication process and photograph of the patterned substrate

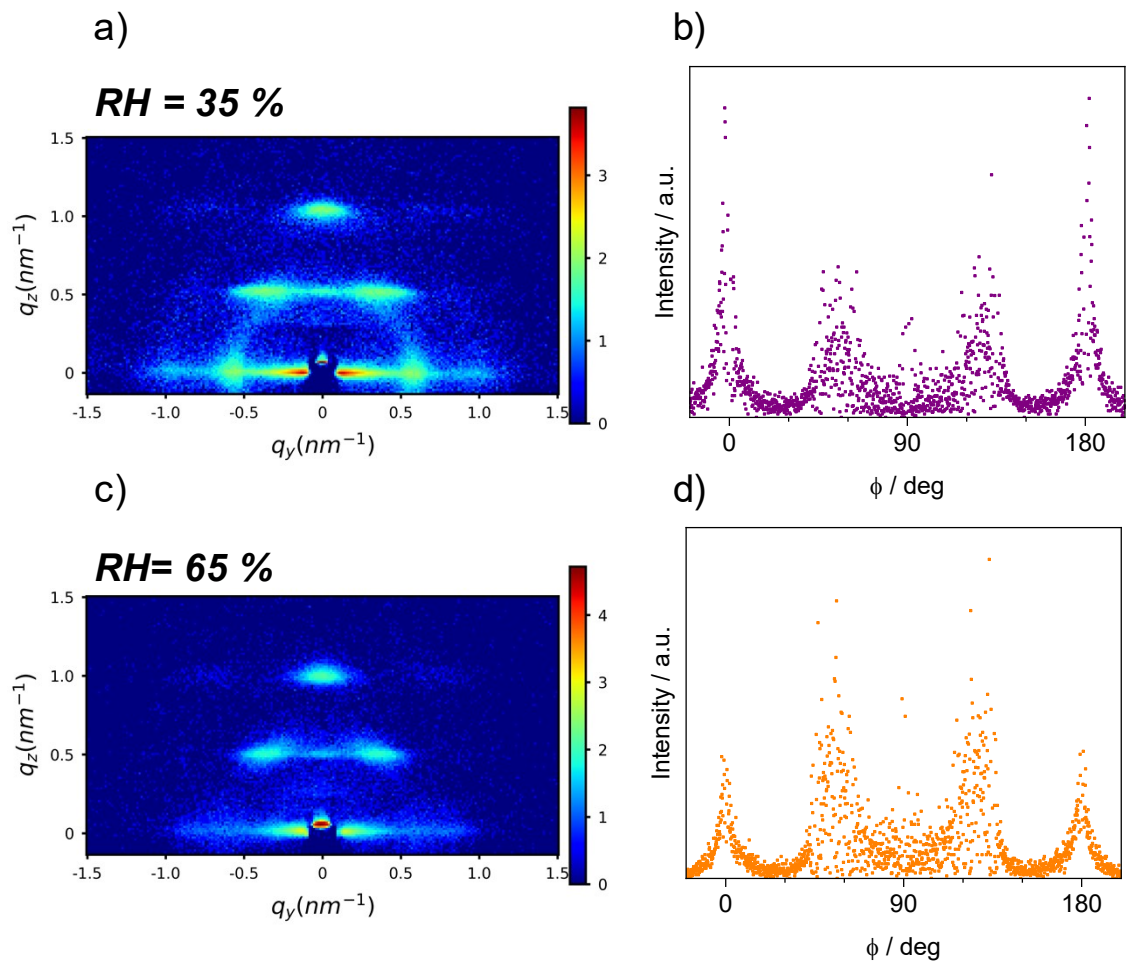


Figure S2- GT-SAXS patterns and the corresponding azimuthal integrations of M-02-35-LiCl (a, b) and M-02-65-LiCl (c, d)

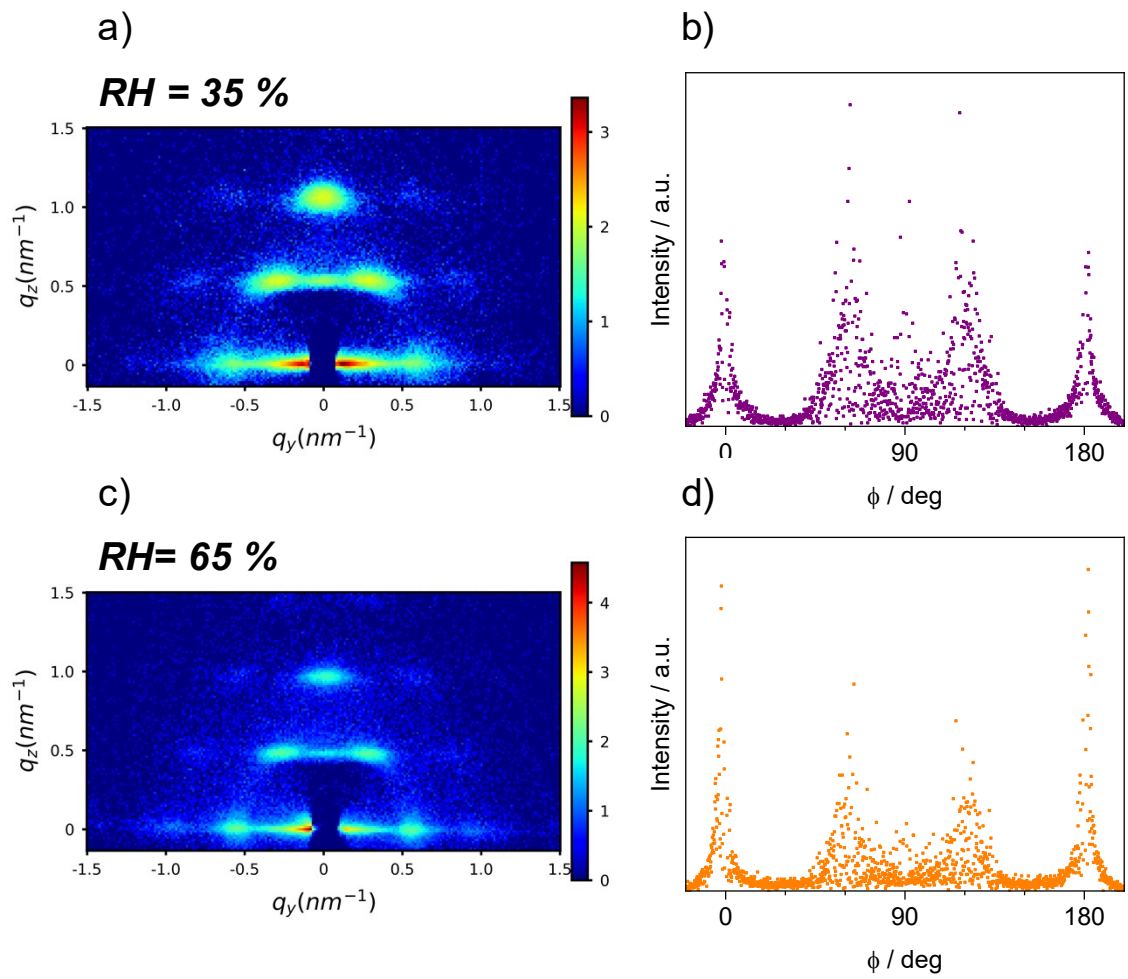


Figure S3- GT-SAXS patterns and the corresponding azimuthal integrations of M-04-35-LiCl (a, b) and M-04-65-LiCl (c, d)

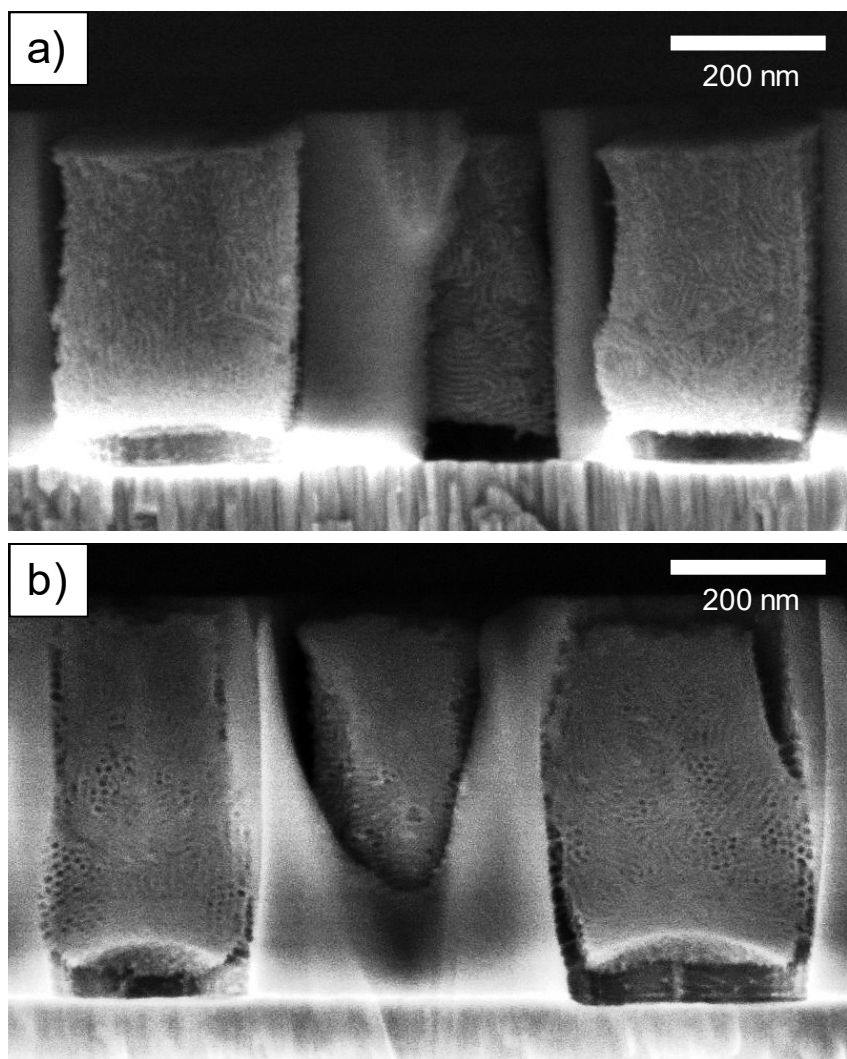


Figure S4- Cross section SEM images of S-04-55-LiCl a) as cleaved and b) ion-milled

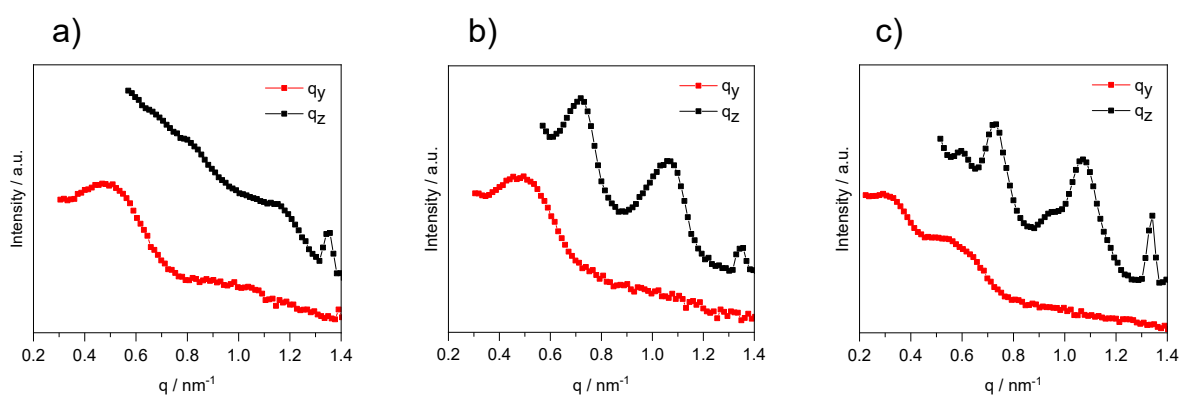


Figure S5- Horizontal (q_y) and vertical (q_z) linecut signals obtained from the GI-SAXS pattern of a) S-04-55-LiCl, b) S-04-55 and c) S-02-55

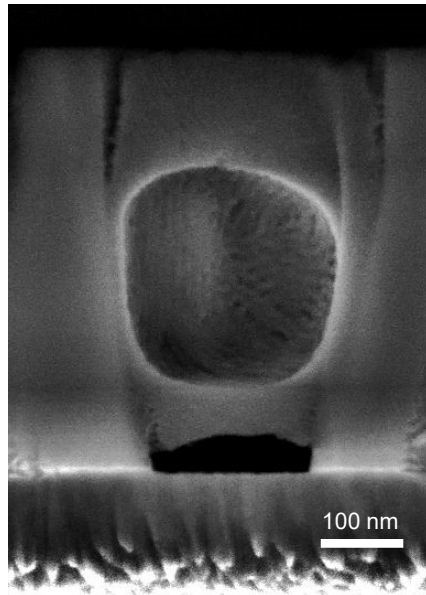


Figure S6- Cross-section SEM image of ion-milled S-04-55-LiCl evidencing a dewetting phenomenon leading to the formation of hole into the mesoporous silica film